



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Karola Richter et al.

Serial No: 10/553,728

Art Unit: 1765

Filing Date: October 14, 2005

Title: SILICON SUBSTRATE COMPRISING POSITIVE ETCHING
PROFILES WITH A DEFINED SLOPE ANGLE AND PRODUCTION
METHOD

Examiner: Patricia Ann George

October 12, 2007

Attorney's Docket No.: HMP201A2

AMENDMENT

Hon. Commissioner of Patents and Trademarks

P.O. Box 1450, Alexandria, VA 22313

SIR:

This is in response to the Office Action mailed on September 24, 2007, and setting a shortened statutory period for response of thirty days to expire on October 24, 2007. Applicants petition that, if required, the time for response be extended and the corresponding fee be charged. The Commissioner is hereby authorized to charge any additional fees which may be required to Acct. No. 11-0224. Applicants further respectfully request that this response be accepted as a bona fide effort to meet any potential response requirements outstanding and due in the above captioned matter.

Please amend the application as follows: